UNITED STATES PATENT AND TRADEMARK OFFICE **CERTIFICATE OF CORRECTION**

PATENT NO.

: 7,183,220 B1

Page 1 of 1

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INVENTOR(S)

: Guy T. Blalock, David S. Becker and Kevin G. Donohoe

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 1, BACKGROUND OF THE INVENTION, line 57

Please replace "the photoresist from the"

With -- the photoresist from --

Column 1, BACKGROUND OF THE INVENTION, line 60

Please replace "there is the contact."

With -- there is an approximate 0.025 micron or greater loss in the lateral direction of the contact. --

Column 2, BACKGROUND OF THE INVENTION, line 7

Please replace "the invention only be limited by the"

With -- the invention only being limited by the --

Column 3, line 66

Please replace "etching conducted"

With -- etching is conducted --

Signed and Sealed this

Sixteenth Day of September, 2008

JON W. DUDAS

Director of the United States Patent and Trademark Office